

S/N TBD
Docket: CS02-099
Group art unit : ___ TBD

Date October 23, 2003

To: Commissioner of Patents and Trademarks
P.O. Box 1450 Alexandria, VA 22313-1450

Fr: William J. Stoffel Reg. No. 39,390 Cust No. 30402
PMB 455
1735 Market St - Suite A
Philadelphia, PA 19103

Subject:

Serial No. TBD
Docket cs02-099
File Date: with application
Inventor: Tan et al.

title: : Method For Dual Damascene Patterning With
Single Exposure Using Tri-Tone Phase Shift Mask

Group art unit: TBD

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO A820 (also PTO-1449), Information
Disclosure Citation and references.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the
United States Postal Service as first class mail in an envelope addressed
to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450, on
oct 24, 2003.

WJS

Signature/Date

William J. Stoffel

William J. Stoffel Reg. No. 39,390
Customer number 30402

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The following Patents and/or Publication are submitted to comply with the duty to disclose under CFR 1.97-1.99 and 37 CFR 1.56.

US 6,482,554 (Matsunuma) shows a for a method for a dual damascene pattern.

US 5,906,910 (Nguyen et al.) shows a method for a dual damascene pattern.

US 6,355,399b1 (Sajan et al.) shows a method for a dual damascene pattern.

US 6,242,344 (Koh et al.) shows a double exposure Tri-layer resist.

US 5,753,417 (Ulrich) shows a dual damascenes process using multiple exposures of one photoresist layer.

Sincerely,



William J. Stoffel

Reg. No. 39,390

Customer number 30,402

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>	Docket Number (Optional) CS02-099	Application Number
	Applicant(s)	
	Filing Date	Group Art Unit

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		US 6,482,554		Matsunuma			
		US 5,906,910		Nguyen et al.			
		US 6,355,399b1		Sajan et al			
		US 6,242,344		Koh et al			
		US 5,753,417		Ulrich			

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.